



EV549570797

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Patent Application Serial No. .... 10/615,051  
Filing Date ..... July 7, 2003  
Inventorship ..... Brian A. Vaartstra  
Assignee ..... Micron Technology, Inc.  
Group Art Unit ..... 2823  
Examiner ..... Brook Kebede  
Attorney's Docket No. .... MI22-2308  
Customer No. .... 021567  
Title: Methods of Forming a Phosphorus Doped Silicon Dioxide-Comprising Layer

**SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT**

References - See Attached Form PTO-1449


In compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, your attention is directed to the United States patents and other references listed on the attached Form PTO-1449. Pursuant to FEDERAL REGISTER, Vol. 69, No. 182, pg. 56542 (September 21, 2004), no copies of any cited U.S. patents or U.S. published applications are included herewith. Copies of all other cited art are attached. No admission is made regarding whether all the submitted references are prior art.

This Supplemental Information Disclosure Statement is being filed before the mailing of a first office action after the filing of a Request for Continued Examination. Therefore, no fee is believed to be required. However, in the event that a fee is required for filing this Supplemental Information Disclosure Statement, please charge the fee specified under 37 C.F.R. § 1.17(p) to Deposit Account No. 23-0925.

Respectfully submitted,

Dated: 5-4-05

By:   
Mark S. Matkin, Reg. No. 32,268

Form PTO-1449	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTORNEY DOCKET NO. MI22-2308	SERIAL NO. 10/615,051
 LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)		APPLICANT: Brian A. Vaartstra	
		FILING DATE 7/7/2003	GROUP ART UNIT 2823

U.S. PATENT DOCUMENTS							
*Examiner's Initials		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	6,013,583	1/11/2000	Ajmera et al.			
	AB	2001/0041250 A1	11/2001	Hauka et al.			
	AC	2002/0000195 A1	1/2002	Kao et al.			
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	AE	2003/0032281 A1	2/13/2003	Werkhoven et al.			
	AF	5,770,469	6/1998	Uram et al.			
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	AH						

FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AI	EP 0817251 A	1/1998	EPO				
	AJ							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)		
	AK	PCT/US2004/021156; Filed 6/30/2004; Search Report.
	AL	PCT/US2004/021156; Filed 6/30/2004; Written Opinion Issued on 1/18/2005; 6 pps.
EXAMINER	DATE CONSIDERED	
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Form PTO-1449	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. MI22-2308	SERIAL NO. 10/615,051
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)		APPLICANT: Brian A. Vaartstra	
		FILING DATE 07/07/2003	GROUP 2823

U.S. PATENT DOCUMENTS							
*Examiner's Initials		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA						
	AB						
	AC						
	AD						
	AE						

FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AF							
	AG							
	AH							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)			
	AI		Chen et al., <i>Excimer Laser-Induced Ti Silicidation to Eliminate the Fine-Line Effect for Integrated Circuitry</i> <i>Device Fabrication</i> , 149 JOURNAL OF ELECTROCHEMICAL SOCIETY, No. 11, pp. G609-G612 (2002).
	AJ		Nishiyama et al., <i>Agglomeration Resistant Self-Aligned Silicide Process Using N<sub>2</sub> Implantation into TiSi<sub>2</sub></i> , 36 JPN. J. APPL. PHYS., Part 1, No. 6A, pp. 3639-3643 (June 1997).
	AK		Wolf, <i>Chapter 13: Polycides and Salicides of TiSix, CoSi<sub>2</sub>, and NiSi</i> , SILICON PROCESSING FOR THE VLSI ERA, Vol. IV, pp. 603-604 (pre-2003).
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